

Title (en)

LOW SURFACE ROUGHNESS POLISHING PAD

Title (de)

POLIERKISSEN MIT GERINGER OBERFLÄCHENRAUHGKEIT

Title (fr)

TAMPON DE POLISSAGE À FAIBLE RUGOSITÉ DE SURFACE

Publication

EP 3007858 A4 20170308 (EN)

Application

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- US 201313917422 A 20130613
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Abstract (en)

[origin: US2014370788A1] The invention provides a polishing pad comprising a polishing pad body comprising a polishing surface, wherein the polishing body comprises pores, and wherein the polishing surface has a surface roughness of about 0.1 μm to about 10 μm .

IPC 8 full level

B24B 37/20 (2012.01); **B24B 37/26** (2012.01)

CPC (source: EP US)

B24B 37/205 (2013.01 - EP US); **B24B 37/26** (2013.01 - EP US)

Citation (search report)

- [XII] US 2009075568 A1 20090319 - KIMURA TSUYOSHI [JP], et al
- [XII] WO 0191972 A1 20011206 - RODEL INC [US]
- [A] WO 2012068428 A2 20120524 - CABOT MICROELECTRONICS CORP [US], et al
- See references of WO 2014200726A1

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DOCDB simple family (publication)

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